類組:電機類 科目:固態電子元件(300G)

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請在答案卷內作答

1. For a material of with E-k diagram shown in **Figure 1**, there are two different effective masses (heavy / light) for electrons. Which effective mass will be the one displayed by most electrons in the conduction band? Explain why? (10%)

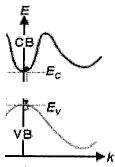


Figure 1

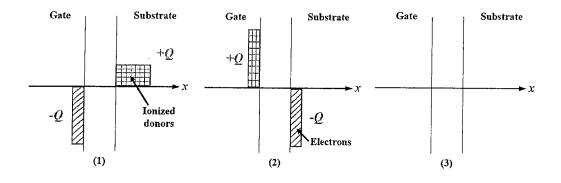
- 2. (a) Please draw two curves of electron mobility vs. temperature (K) in log-scale for two Si samples, A and B with uniform doping concentrations of N_{D1} , N_{D2} , respectively, where $N_{D1} < N_{D2}$. Please label A and B on the plot. (10%) (b) Sample B is counter-doped uniformly with N_A , becoming sample C. Draw its mobility vs. temperature curve on the same plot in (a) and explain the differences in the 3 corresponding curves. (10%)
- 3. We deposit a metal with a work function of 4.6 eV on Si at room temperature. Suppose that the Si has an electron affinity of 4 eV and a doping concentration of 10¹⁷ cm⁻³. Please draw the equilibrium band diagrams of this M-S junction if (a) the doping is n-type and (b) the doping is p-type, respectively. (20%)
- 4. Consider a uniformly doped Si NPN BJT. For the emitter and base regions, assume equal region widths ($x_E=x_B$), diffusion lengths ($L_E=L_B$), and minority carrier lifetimes ($\tau_E=\tau_B$). With doping concentrations $N_B=10^{17}$ cm⁻³ and $N_E=10^{19}$ cm⁻³, please calculate the emitter injection efficiency when the bandgap narrowing effect is neglected. (15%)
- 5. Consider a MOS capacitor fabricated on an n-type silicon. The charge diagrams for this MOS capacitor under various bias conditions are shown in diagram (1)-(5) of **Figure 2**.
 - (a) Which charge diagram corresponds to accumulation condition? (3%)
 - (b) Which charge diagram corresponds to depletion condition? (3%)
 - (c) Which charge diagram corresponds to strong-inversion condition? (3%)

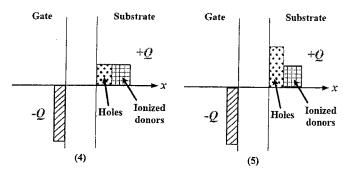
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- (d) Which charge diagram corresponds to flat-band condition? (3%)
- (e) Which charge diagram corresponds to threshold condition? (3%)





- Figure 2
- 6. For an NMOSFET, assume that the gate oxide thickness $t_{ox} = 277$ Å, the channel length L = 1 µm, the channel width W = 10 µm, and the threshold voltage $V_T = 1$ V and the saturation velocity of the electron $v_{sat} = 8 \times 10^6$ cm/s. The output characteristics of the transistor with $V_{GS} = 5$ V were measured and three data points are given here. Note that $I_D = WQ_n(y)v(y)$ and that we have $C_{ox} = 1.25$ F/m² for $t_{ox} = 277$ Å
 - (a) What are the electron velocities at the source end of the channel and at the drain end of the channel for data point A, $V_{DS} = 0.5 \text{ V}$, $I_D = 1.0 \text{ mA}$? (5%)
 - (b) What are the electron velocities at the source end of the channel and at the drain end of the channel for data point B, $V_{DS} = 2.5 \text{ V}$, $I_D = 2.5 \text{ mA}$? (5%)
 - (c) What are the electron velocities at the source end of the channel and at the drain end of the channel for data point C, $V_{DS} = 5.0 \text{ V}$, $I_D = 2.75 \text{ mA}$? (5%)
 - (d) It appears from above findings that the drain current saturated well before V_{DS} reach $V_{Dsat} = V_{GS} V_T = 4$ V as predicted by the basic MOSFET I-V model. Why does the current saturation happen before $V_{DS} = 4.0$ V? (5%)